

1/6

FIG. 1

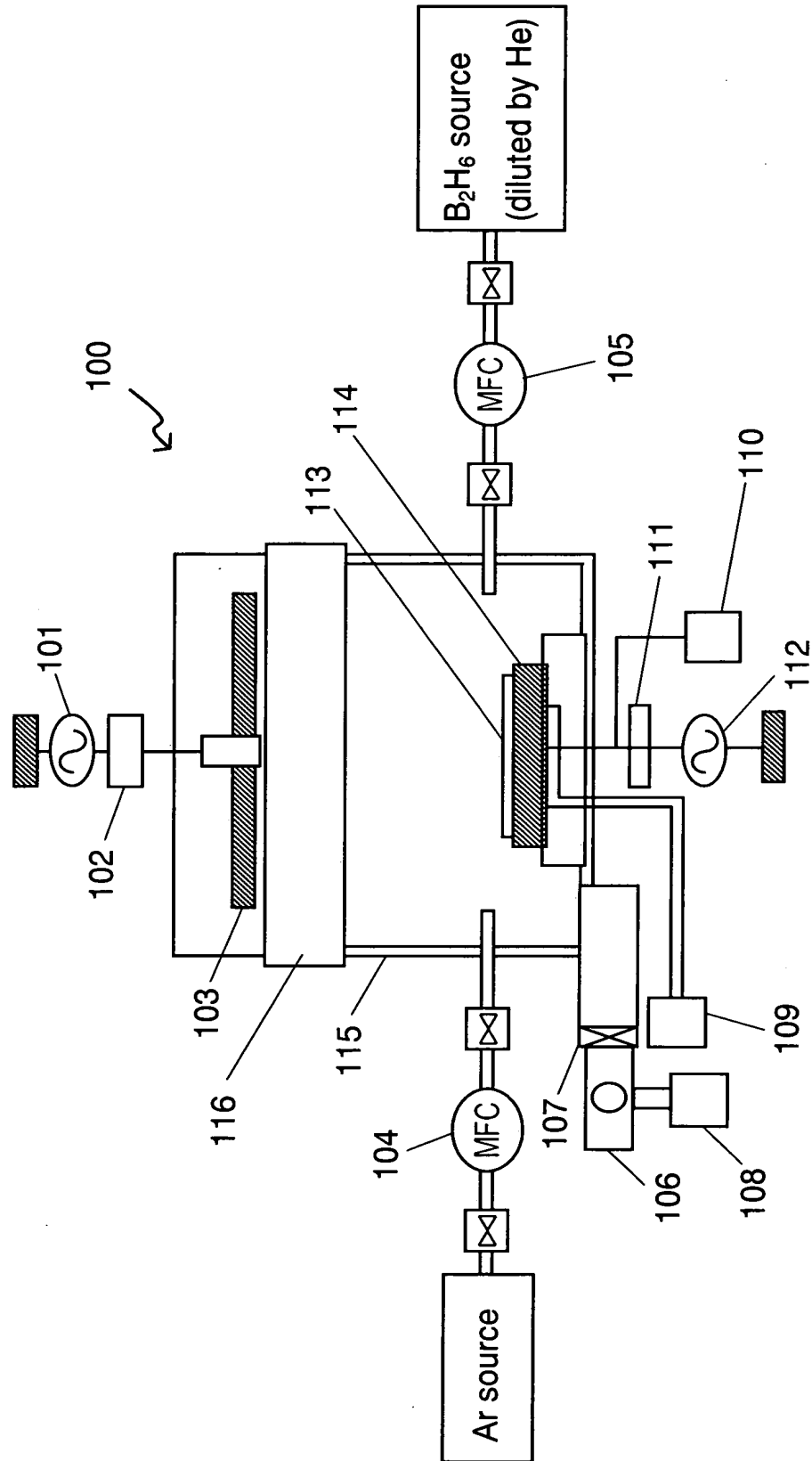
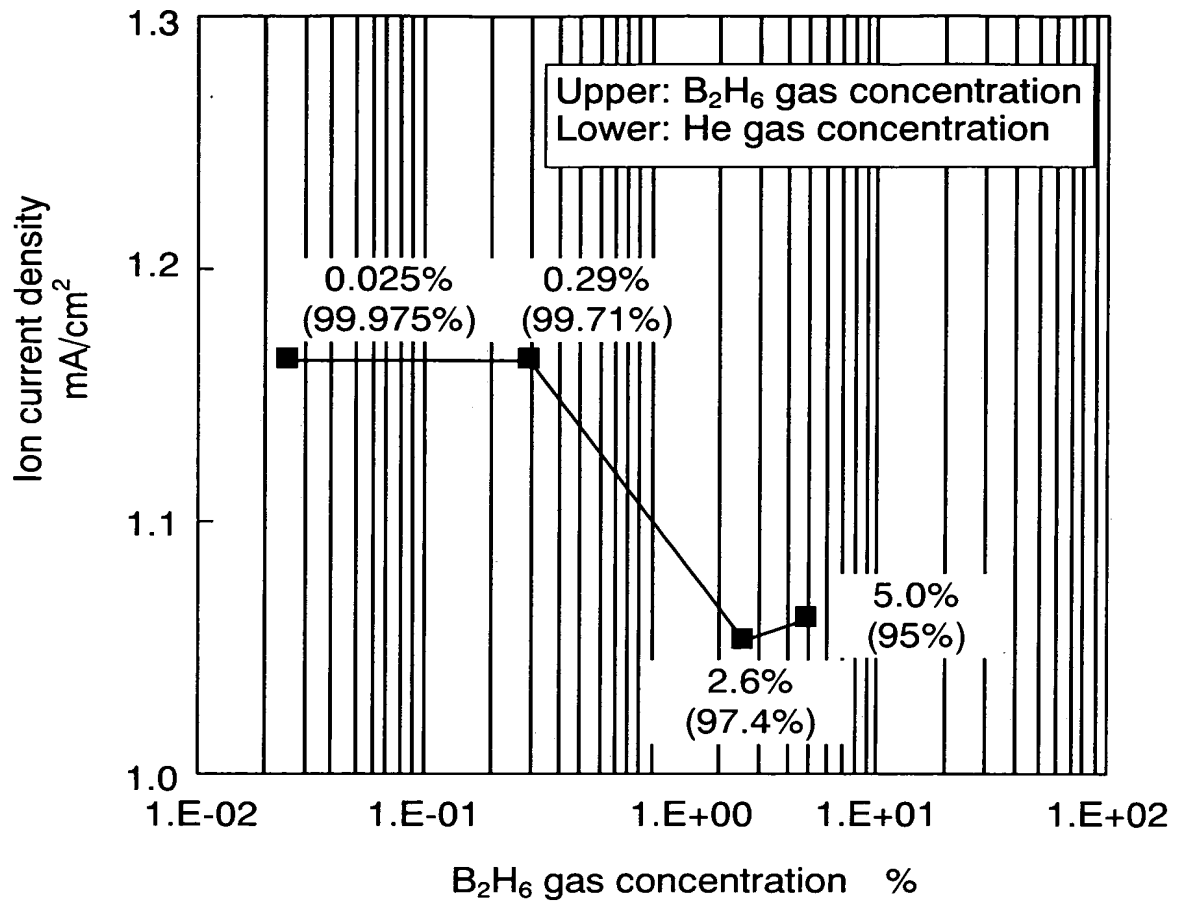


FIG. 2



3/6

FIG. 3

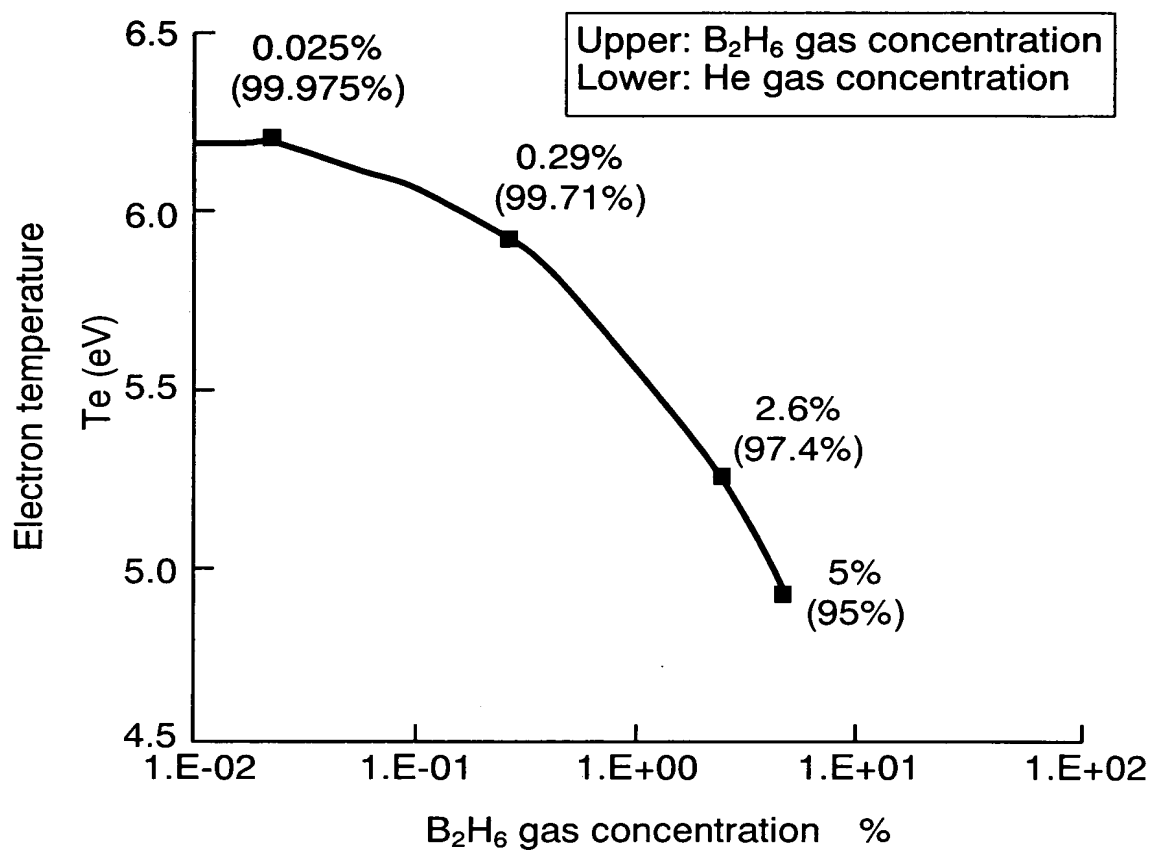


FIG. 4

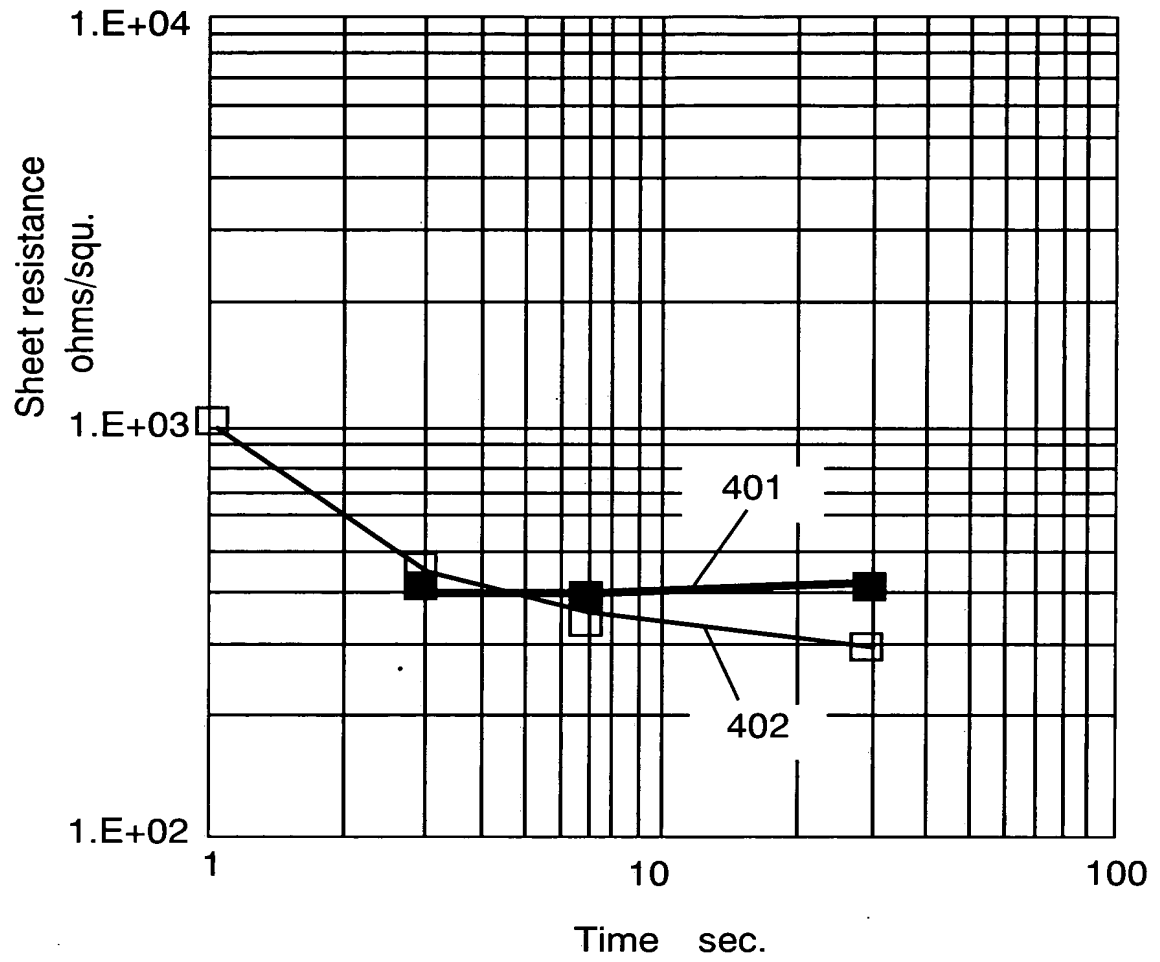


FIG. 5A

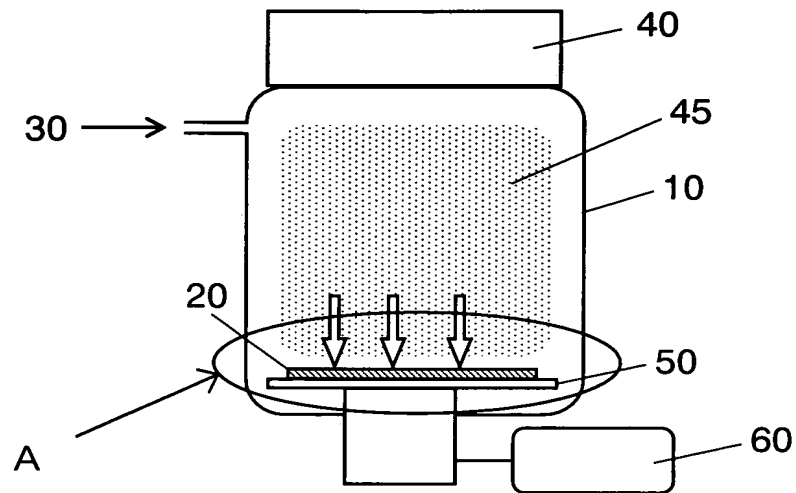
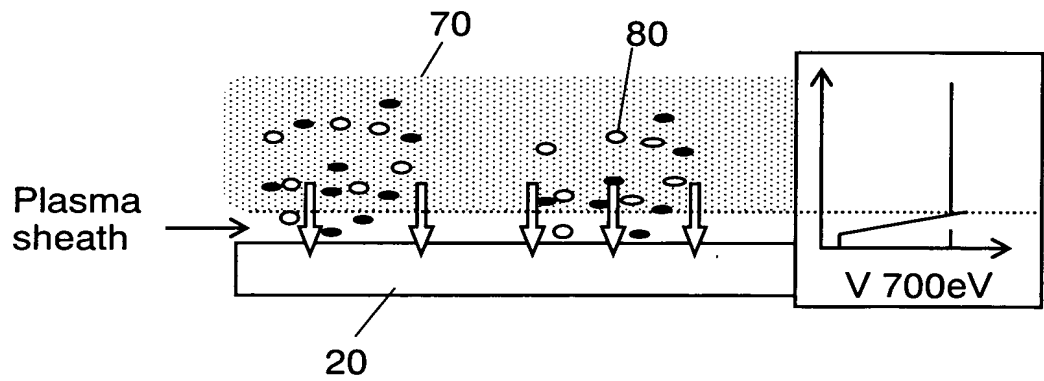


FIG. 5B



## Reference marks in the drawings

10	Reactor chamber
20	Silicon wafer
30	B <sub>2</sub> H <sub>6</sub> gas
40	ECR plasma source
45	Plasma
50	Wafer susceptor
60	RF power supply
100	Plasma doping apparatus
101	High-frequency power supply
102	Matching box
103	Coil and antenna
104	Mass-flow controller
105	Mass-flow controller
106	Turbo pump
107	Conductance valve
108	Dry pump
109	Circulator
110	DC power supply
111	Matching box
112	High-frequency power supply
113	Target
114	Susceptor
115	Reactor chamber
116	Glass member
401, 402	Plotted line indicating the relation between voltage application time and sheet resistance